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Bib Data Sheet

CONFIRMATION NO. 1510

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|-----------------------------|---------------------------------------|--------------|------------------------|---|
| SERIAL NUMBER 10/522,036 | FILING DATE 01/19/2005 RULE | CLASS 430 | GROUP ART UNIT 1752 | ATTORNEY DOCKET NO. SHIGA7.004APC |
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**** CONTINUING DATA *******
 This application is a 371 of PCT/JP04/07139 05/19/2004 SJL

**** FOREIGN APPLICATIONS *******
 JAPAN 2003141805 05/20/2003) SJL
 JAPAN 2003426503 12/24/2003)

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|---|------------------------------|------------------------|-----------------------|----------------------------|
| Foreign Priority claimed <input checked="" type="checkbox"/> yes <input type="checkbox"/> no | STATE OR COUNTRY JAPAN | SHEETS DRAWING 0 | TOTAL CLAIMS 38 | INDEPENDENT CLAIMS 4 |
| 35 USC 119 (a-d) conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance | | | | |
| Verified and Acknowledged Examiner's Signature: <i>[Signature]</i> Initials: SJL | | | | |

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TITLE
 Chemically amplified positive photo resist composition and method for forming resist pattern